

SILPAK, Inc

470 E. BONITA AVE., POMONA, CA 91767
PH (909) 625-0056 WWW.SILPAK.COM FX (909) 625-0082

Classic Clay Product Data Sheet

Classic Clay is a versatile and unique wax based sculpting clay that was developed to meet the needs of artists and model-makers. As a sculpting medium, this material provides the user with an easily workable material from which an original or master pattern can be produced---**Medium and Hard versions** are available. An added benefit of this material is that it can be melted and poured into a mold (Silicone RTV) to reproduce a pattern or master. It can also be used as a master pattern to produce RTV silicone molds. **Classic Clay** does not contain sulfur and is easily heat-controlled to vary working hardness. Use alcohol or mineral spirits to smooth out.

Available Sizes: Slab (8-11#), Case 50 lb

Color: Brown or Tan

Hardness: Medium & Firm

Melting Temp: 180F - 200F

PROCESSING AND HANDLING INSTRUCTIONS:

Classic Clay is wax based and easily smoothes out with alcohol. **Medium** hardness is ideal for most applications and is preferred by many artists to create sculptures of fine quality. It is recommended that this product be kept between 180F and 200F when melting. **Do not exceed 250°F** and caution with open flame heat source. It may be softened with incandescent-light bulb, heat lamp, heat gun, or can be heated in an oven @ 200F to create pourable liquid which will ultimately harden when allowed to cool. Once melted, material can be poured into a mold or painted on a warm surface to fill-in areas.

CAUTION:

Care must be taken never to heat the product above 250F as it contains wax and will flash and burn above this temperature. Handling hot material requires the use of proper heat resistant work gear.

THE INFORMATION AND DATA CONTAINED HEREIN ARE BASED ON INFORMATION WE BELIEVE RELIABLE. EACH USER OF THE MATERIAL SHOULD THOROUGHLY TEST ANY APPLICATION, AND INDEPENDENTLY CONCLUDE SATISFACTORY PERFORMANCE BEFORE COMMERCIALIZING. SUGGESTIONS OF USES SHOULD NOT BE TAKEN AS INDUCEMENTS TO INFRINGE ON ANY PARTICULAR PATENT.